Characterizing Plastic Deformation Mechanisms in Metal Thin Films using in situ TEM Nanomechanics

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# Increased MEMS market drives demand for reliable nanomaterials

### MicroElectroMechanical Systems (MEMS) Global Market





Metallic thin films used for:

- Structural coatings
- Electrical contacts



Optimize mechanical properties of metal thin films



# Fine-grained metals pose as viable solution to high-strength & radiation tolerant materials

Ultrafine-grained (UFG): 100 nm > d > 1 $\mu$ m Nanocrystalline (NC): d < 100 nm

NC & UFG metals exhibit unique properties due to the high-volume fraction of grain boundaries (GBs):



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NC & UFG metals exhibit unique properties due to the high-volume fraction of grain boundaries (GBs):





Enikeev et al. Mat. Trans. 60 (2019) 1723-1731

Grain boundaries are a site for defect absorption  $\rightarrow$  defect denuded zone





Cheng et al. Acta Mat. 51 (2003) 4505-4518



### **Traditional grain size regime**



Boioli et al. Mult. Mod. of Mantle Rheology (2018)

Cheng et al. Acta Mat. 51 (2003) 4505-4518

Grain boundary- based deformation:

- GB sliding
- Grain rotation
- GB migration







### Traditional grain size regime



Boioli et al. Mult. Mod. of Mantle Rheology (2018)

Meyers et al. JOM (2006) 41-48

Cheng et al. Acta Mat. 51 (2003) 4505- 4518



Cheng et al. Acta Mat. 51 (2003) 4505-4518

Yu et al. MRS Bulletin 40 (2015) 62-48

## Three approaches required to fully characterize deformation mechanisms



# Deformation mechanisms can be characterized by Activation Volume V\*

Activation volume is a signature parameter associated with dislocation mechanisms



# Activation Volume V\* measured experimentally by performing repeated stress-relaxation experiment



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# Working parameters of MEMS devices used to conduct experiments



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# *in situ* straining and mechanical testing data

Direction of applied load



# **Specimen fabrication cleanroom process flow**





Deposition + Lift Off

E-beam evaporation

Thickness ~ 100-200 nm



### Irradiation

A portion of Au specimens at the Sandia National Laboratory IBL facility

> Irradiation parameters: 2.8 MeV Au+ ionsfluence  $5.5 \times 10^{13}$ ions/cm<sup>2</sup> ~1 dpa

### Release

## Free-standing thin films



# **Specimen fabrication cleanroom process flow**



# Characterizing and comparing behavior of as-deposited (non-irradiated) and irradiated ultrafine-grained gold

Many radiation

induced defects



- Few defects



Irradiation parameters: 2.8 MeV Au+ ~1 dpa



# As-Deposited Au: Variety of deformation mechanisms active



based mechanisms active

Which is rate-controlling?

# Irradiated: Increased strength and decreased ductility due to radiation damage-induced dislocation pinning



# Stress-induced grain boundary migration leads to defect free regions





100 nm

# Stress-induced grain boundary migration leads to defect free regions





 Defect free regions can now support extended dislocation glide

### Which is rate-controlling?

## Three approaches required to fully characterize deformation mechanisms



## *In situ* TEM Activation Volume V\* measurements



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# **UFG Au: All V\* Measurements**



## Three approaches required to fully characterize deformation mechanisms



# **FENEB** calculations of dislocation mechanisms give $V^* > 15b^3$



### **Grain boundary dislocation nucleation**

(b2)

(b4)

Au

Al Cu

0.5

1.0

1.5

Activation energy (eV)

2.0

2.5

3.0

# **FENEB** calculations of dislocation mechanisms give $V^* > 15b^3$



#### Zhang, Ding et al., Acta Mat. 237 (2022) 118155

# Scaling required to account for grain size difference

- ➢ Experimentally: grain size ~ 140 − 760 nm
- Simulations: grain size ~ 10 nm

Hall-Petch-type relationship between grain size (d) and  $V^*$ :

Conrad's model:



# **Dislocation nucleation processes cannot explain low V\* values**





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What's next?? Working on R&D for Radar systems!

